### PHYSICS AND CHEMISTRY OF SOLID STATE

V. 22, No. 1 (2021) pp. 80-87

Section: Physics

DOI: 10.15330/pcss.22.1.80-87

ФІЗИКА І ХІМІЯ ТВЕРДОГО ТІЛА Т. 22, № 1 (2021) С. 80-87

Фізико-математичні науки

PACS: 61.72.Cc, 64.75.Op, 66.30.Dn, 66.30.Ny, 66.30.Pa, 68.35.Fx, 68.35.Rh

ISSN 1729-4428

M.V. Yarmolenko

## Intermetallics Disappearance Rates and Intrinsic Diffusivities Ratios Analysis in the Cu-Zn and the Cu-Sn Systems

Kyiv National University of Technologies and Design, Faculty of Market, Information and Innovation Technologies, Cherkasy, Ukraine, <u>varmolenko.mv@knutd.edu.ua</u>

Intermetallics disappearance rates and intrinsic diffusivities ratios in the Cu-Zn system at temperature 400 °Cand in the Cu-Sn system at temperatures from 190 °C to 250 °C are analyzed theoretically using literature experimental data. Diffusion activation energies and pre-exponential coefficients for the Cu-Sn system are calculated combining literature experimental results.

Keywords: diffusion, intermetallics, phases formation kinetics, copper, zink, tin, Kirkendall-Frenkel porosity, Kirkendall shift.

Received 3 February 2021; Accepted 20 February 2021.

#### Introduction

A theoretical method to describe intermetallics disappearance rate in double multiphase systems was proposed in [1], and intermetallics disappearance rates in the Al-Cu system at temperatures from 175 °C to 225 °C were analyzed. Ref. 2 reported on another theoretical method of calculation the ratio of intrinsic diffusivities in double multiphase systems, and intrinsic diffusivities ratios of copper and aluminum in the Al-Cu system were calculated at temperatures from 400 °C to 535 °C and at temperatures less than 100°C. Both methods are confirmed experimentally during the investigation the Cu-Zn system at temperature 400 °C [5, 8].

The soldered copper/tin based contacts are the weakest part of the chip that can be related to intermetallics and the Kirkendall-Frenkel porosity formation in the contact zone [3, 4, 7]. One of the most common reasons for chip failure is the soldered. The typical range of packaging and operation of the integrated circuits is from room temperature up to  $250 \,^{\circ}$ C [32]. Therefore, it is very important to analyze the intermetallics disappearance rates and intrinsic diffusivities ratios in the Cu-Sn systems at temperatures from 190 °C to  $250 \,^{\circ}$ C.

## I. Intermetallics disappearance rate analysis

#### I.1. The Zn-Cu system

We didn't analyze intermetallics disappearance rate in the Zn-Cu system [5, 8], so we can do it now. Three phases ( $\varepsilon$ -brass, Zn<sub>5</sub>Cu,  $C_1 \approx 0.83$ ;  $\gamma$ -brass, Zn<sub>8</sub>Cu<sub>5</sub>,  $C_2 \approx 0.62$ ; and  $\beta$ -brass, ZnCu,  $C_3 \approx 0.5$ ,  $C = C_{Zn}$ ) are formed during diffusion. Reaction rates of phases formation at temperature 400 °C were measured:  $K_1 \approx 2025 \ \mu m^2/h$ ,  $K_2 \approx 14400 \ \mu m^2/h$ ,  $K_3 \approx 160 \ \mu m^2/h$ ,  $K_2 \approx 7K_1$ ,  $K_3 \approx 0.08K_1 \approx 0.011K_2$ . Initial Zn covering thickness was  $X_A \approx 115 \ \mu m$ . Eqs.9 in [1] give:

$$K_{123} = \left(\sqrt{K_1} + \sqrt{K_2} + \sqrt{K_3}\right)^2 \approx 31500 \ \mu m^2/h$$
$$K_{12} = \left(\sqrt{K_1} + \sqrt{K_2}\right)^2 \approx 27200 \ \mu m^2/h$$

 $(K_3 < < K_1 \text{ and } K_3 < < K_2)$ . Zinc disappearance time,  $t_0$ , at temperature 400°C can be estimated by Eq.11 [1]:

$$t_0 = \frac{X_{Zn}^2}{(C_1\sqrt{K_1} + C_2\sqrt{K_2} + C_3\sqrt{K_3})^2} \approx 0.94h \approx \frac{X_{Zn}^2}{C_1^2 K_{12}} \approx 0.7h.$$
(1)

The value  $t_0=0.94h$  exactly corresponds with the experimentally obtained one [8]  $t_0=0.92h$  in planar

samples. Phase 1 ( $\epsilon$ -brass, Zn<sub>5</sub>Cu) disappearance time,  $t_1$ , can be estimated by Eq.13 [1]:

$$t_1 = \frac{X_{Zn}^2}{(C_2 \sqrt{K_2^{(2\,phases)}} + C_3 \sqrt{K_3^{(2\,phases)}})^2} \approx 2h \approx \frac{X_{Zn}^2}{C_2^2 K_{12}} \approx 1.3h.$$
(2)

Such values correspond to experimental result [8]:  $t_1 = 1.64 h$  in cylindrical samples.

#### I.2. The Cu-Sn system

Two phases are formed in the Cu-Sn system during isothermal annealing of Cu/Sn samples at temperature  $T = 200 \,^{\circ}\text{C}$  [3, 6, 9]:  $\epsilon$ -phase Cu<sub>3</sub>Sn (phase 1,  $C_1 \approx {}^{3}\!\!/_4 = 0.753$ ,  $\Delta C_1 = 0.012$ ,  $C = C_{Cu}$  [6]) and  $\eta$ -phase Cu<sub>6</sub>Sn<sub>5</sub> (phase 2,  $C_2 \approx 6/11 = 0.547$ ,  $\Delta C_2 = 0.021$ ,  $C = C_{Cu}$  [6]), at temperature  $T = 210 \,^{\circ}\text{C}$  [10], and at temperature  $T = 250 \,^{\circ}\text{C}$  (Sn is liquid) [11]. Parabolic growth constants for the layer thicknesses were measured in [6], also the range of homogeneity of each phase were measured, and the values of the mutual diffusion coefficients for the Cu<sub>3</sub>Sn (phase 1) and Cu<sub>6</sub>Sn<sub>5</sub> (phase 2) phases between 463 K and 493 K (190  $\,^{\circ}\text{C}$  and 220  $\,^{\circ}\text{C}$ ) were calculated too:

$$\tilde{D}_1^* = 1.43 x 10^{-8} e^{-70.7 k J mol^{-1}/(RT)} m^2 / s , \qquad (3)$$

$$\tilde{D}_2^* = 1.55 \times 10^{-8} e^{-64.9 k J mol^{-1}/(RT)} m^2 / s , \qquad (4)$$

and for phase 1 only (Cu/Cu\_6Sn\_5 sample) between 630 K and 677 K (357  $^{\rm o}C$  and 404  $^{\rm o}C$ ):

$$\tilde{D}_{1}^{*(1\,phase)} = 1.09 x 10^{-6} e^{-78.2 k J mol^{-1}/(RT)} m^{2} / s \,. \tag{5}$$

We can calculate the mutual diffusion penetrability (or Wagner diffusivity [26]) of each phase,  $D_i$ , taking into account that  $D_i = D_i^* \Delta C_i$  and  $\Delta C_i$  depends on temperature [6]:

 $\Delta C_{l} = 0.014 (190 \text{ °C}) = 0.018 (210 \text{ °C}) = 0.010 (220 \text{ °C}),$  $\Delta C_{2} = 0.023 (190 \text{ °C}) = 0.022 (210 \text{ °C}) = 0.017 (220 \text{ °C}),$  $\Delta C_{l}^{(lphase)} = 0.005 (357 \text{ °C}).$  Mutual diffusion penetrabilities of phase 1 can be calculated by Gibbs's method [12] or by "constant flux method" (Gurov's and Gusak's method) [13-23] or by other methods [26, 28-30] (data are from [6] as an example):

$$D_1 \approx \frac{1}{2}C_1(1 - C_1)K_1 \approx \frac{3}{32}K_1 \approx 2.5x10^{-18}m^2 / s \approx \left\{2.1x10^{-18}m^2 / s[6], T = 190^o C\right\}.$$
 (6)

Mutual diffusion penetrabilities of phase1 and phase 2 can be calculated by "constant flux method" (data are

from [9] as an example):

$$D_{1} \approx \frac{1}{2} (C_{1}(1-C_{1})K_{1} + C_{2}(1-C_{1})\sqrt{K_{1}K_{2}}) \approx \\ \approx \frac{3}{32} K_{1} + \frac{3}{44} \sqrt{K_{1}K_{2}} \approx 29.4 \times 10^{-18} m^{2} / s \approx \left\{ 19.4 \times 10^{-18} m^{2} / s[9] \right\};$$
(7)

$$D_{2} \approx \frac{1}{2} (C_{2}(1 - C_{2})K_{2} + C_{2}(1 - C_{1})\sqrt{K_{1}K_{2}}) \approx \\ \approx \frac{15}{121}K_{2} + \frac{3}{44}\sqrt{K_{1}K_{2}} \approx 53.6x10^{-18}m^{2} / s \approx \left\{56.4x10^{-18}m^{2} / s[9]\right\},$$
(8)

so we can see a good agreement between applied methods (Table 1).

Initial Cu layer thickness [3] can be calculated using mass conservation law (Fig. 1):

 $X_{Cu}(t=0)\approx 5\mu m + C_1 X_1(t) + C_2 X_2(t)\approx 12.4\mu m\,.$ 

Copper layer disappearance time can be calculated using Eq. 1 (Fig. 2):

Table 1

Authors	<i>T</i> , <i>°C</i>	<i>t</i> , <i>h</i>	$K_{1,}$ $x10^{-18}$ $m^{2}/s$	$K_{2,}$ $x10^{-18}$ $m^{2}/s$	$\frac{K_2}{K_1}$	$     D_{1}, \\     x10^{-18} \\     m^{2}/s $	$D_2,$ $x10^{-18}$ $m^2/s$	$\frac{D_2}{D_1}$	$K_1^{(1phase)},$ $x10^{-18} m^2/s$ $Cu/Cu_6Sn_5$ couple	$K_2^{(1phase)},$ $x10^{-18} m^2/s$ $Cu_3Sn/Sn$ couple
Onishi and	190	400	27.2	88.2	3.2	2.1	18	8.6	-	-
Fujibuchi	200	400	38.4	112	2.9	2.6	23.5	9.0	-	-
[6]	210	400	52.1	142	2.7	5.7	34.4	6	-	-
	220	400	74.1	204	2.75	4.5	37	8.2	-	-
	357	16	-	-	-	-	-	-	26900	-
									$D_1^{(1phase)} =$	
									1800	
This work	190	-	-	-	-	6	14.3	2.4	-	-
	200	-	-	-	-	8.1	18.3	2.2	-	-
	210	-	-	-	-	10.7	23.5	2.2	-	-
	220	-	-	-	-	15.3	33.7	2.2	-	-
	357	-	-	-	-	-	-	-	$D_1^{(1 phase)} =$	-
									1500	
Paul et al.	200	225	100	332	3.3	19.4	56.4	2.9		-
[9]										-
This work	-	-	-	-	-	29.4	53.6	1.8	-	-
Kumar <i>et</i>	200	240	20	72	3.6	2.5	18.2	7.2	184	-
<i>ui</i> . [5]						4.5	11.5	26	D.(1phase)_	
This work	-	-	-	-	-	4.5	11.5	2.0	$10.3 \approx D_2$	-
Liashenko <i>et</i> al. [11]	250	8	820	6600	8.0	-	-	-	-	10270
This work	-	-	-	-	-	236	975	4.1	-	$D_2^{(1phase)} = 764 \approx D_2$

Comparison of diffusion penetrabilities calculated by different methods



**Fig. 1.** Change of copper concentration profile during isothermal annealing of a Cu(99.9 %)/Sn couple at temperature  $T = 200^{\circ}$ C within 10 days [3]:  $D^*_{Cu} > D^*_{Sn}$ ,  $D^*_{Sn} \approx 0.31D^*_{Cu}$ ;  $X_1 < X_2$ ,  $X_2 \approx 2X_1$ ,  $X_K \approx 3\mu m$ ;  $C_1 = 3/4$ ;  $C_2 = 6/11$ ,  $C = C_{Cu}$ .

 $t_0 = \frac{X_{Cu}^2}{(C_1 \sqrt{K_1} + C_2 \sqrt{K_2})^2} \approx \frac{154 \times 10^{-12} m^2}{6.4 \times 10^{-17} m^2 / s} \approx 28 days \; .$ 

Phase 2 is formed between phase 1 and tin after disappearance of Cu, phase 1 homogenization occur after this time, concentration decreases from  $C_I$  to  $C_I$ - $\Delta C_I$ , and



**Fig. 2.** Change of copper concentration profile during isothermal annealing at temperature  $T = 200^{\circ}$ C within 28 days (calculation):  $D^*_{Cu} > D^*_{Sn}$ ;  $X_1 < X_2$ ;  $X_2 \approx 2X_1$ ;  $X_K \approx 4.8 \mu m$ ;  $C_1 = 3/4$ ;  $C_2 = 6/11$ ,  $X_{12}$  is boundary between phase 1 and phase 2.

boundary between phase 1 and phase 2,  $X_{12}$ , moves to the left hand direction (see Fig. 2). The boundary moves to the left hand direction also after full homogenization

of phase 1. We can calculate assuming  $C_1 = 3/4$  and  $C_2 = 6/11$  and taking into account Eq. 6:

$$D_2^{(1\,phase)} \approx \frac{C_2(C_1 - C_2)K_2^{(1\,phase)}}{2C_1} \approx \frac{9}{121}K_2^{(1\,phase)} \approx 764 \times 10^{-18} m^2 / s \approx D_2^{(2\,phases)}, \tag{9}$$

as should be expected. Phase 1 layer disappearance time can be calculated using Eq. 2 (Fig. 3):

$$t_1 = \frac{X_{Cu}^2}{C_2^2 K_2^{(1phase)}} \approx 39 days \,.$$

Phase 2 homogenization occur after this time, concentration decreases from  $C_2$  to  $C_2$ - $\Delta C_2$ , and boundary between phase 2 and Sn moves to the left hand direction.

#### I.3. The Sn-Cu system

We can analyze experimental results in the Sn-Cu

system described in [11] (Fig. 4).

Two phases are formed in the Cu-Sn system during isothermal annealing of Cu/Sn samples at temperature T = 250 °C during t = 8 h (Sn is liquid):  $X_1 = 3.97$   $\mu m$ ,  $X_2 = 12.75 \ \mu m$ ;  $K_1 = 8.2 \times 10^{-16} \ m^2/s$ ,  $K_2 = 6.6 \times 10^{-15} \ m^2/s$ ;  $C_2 = 5/11$ ,  $C_1 = 1/4$ ,  $C = C_{Sn}$ . The thickness of tin layer over the Cu and Cu<sub>3</sub>Sn substrates varied from 20 to 200  $\mu$ m. General phases formation rate can be calculated by Eqs. 9 in [1]:

$$K_{12} = \left(\sqrt{K_1^{(2\,phases)}} + \sqrt{K_2^{(2\,phases)}}\right)^2 = 12065 \times 10^{-18} m^2 / s \approx K_2^{(1\,phase)} = 10268 \times 10^{-18} m^2 / s , \qquad (10)$$

so phase 2 growth rate,  $K_2^{(1 \text{ phase})}$ , is approximately equal to initial general growth rate,  $K_{12}$  (Table 1). The disappeared Sn thickness can be estimated:  $X_{Sn}(8h) = C_1 X_1(8h) + C_2 X_2(8h) \approx 6.8 \mu m$ . Tin layer disappearance time can be calculated using Eq.1:

$$t_0(X_{Sn} = 20\mu m) = \frac{X_{Sn}^2}{(C_1\sqrt{K_1} + C_2\sqrt{K_2})^2} \approx 57h \approx 2.4 days;$$
  
$$t_0(X_{Sn} = 200\mu m) = \frac{X_{Sn}^2}{(C_1\sqrt{K_1} + C_2\sqrt{K_2})^2} \approx 240 days \approx 8months.$$



 $X_K \approx 5.7 \, \mu m$ 

**Fig. 3.** Change of copper concentration profile during isothermal annealing at temperature T = 200 °C within 39 days (calculation):  $D^*_{Cu} > D^*_{Sn}$ ;  $X_2 \approx 23\mu m$ ;  $X_K \approx 5.7\mu m$ ;  $C_2 = 6/11 \approx 0.55$ .



Initial interface

**Fig. 4.** Concentration profile of Sn change during isothermal annealing of a Cu (99.99 % purity)/Sn couple at temperature  $T = 250^{\circ}$ C within 8*h* [11]:  $X_2 = 12.75 \mu m$ ,  $X_1 = 3.97 \mu m$ ,  $X_2 \approx 3X_1$ ,  $C_2 = 5/11$ ,  $C_1 = 1/4$ ,  $C = C_{Sn}$ .

#### **II.** Intrinsic Diffusivities Ratio Analysis

#### II.1. The Zn-Cu system

We didn't analyze intrinsic diffusivities ratio in the Zn-Cu system [5], so we can do it now. Three phases can formed: Zn<sub>5</sub>Cu (phase 1,  $C_1 \approx 0.83$ ), Zn<sub>8</sub>Cu<sub>5</sub> (phase 2,  $C_2 \approx 0.62$ ), and ZnCu (phase 3,  $C_3 \approx 0.5$ ,  $C = C_{Zn}$ ) (Fig. 5). Inert markers were in phase 2. Mutual diffusion coefficient in phase 2,  $D^*_2$ , and Kirkendall shift,  $X_K$ , were measured at  $T = 400^{\circ}$ C:  $D^*_2 = 9.1 \times 10^{-12} m^2/s$ , t = 9h,  $X_K \approx 150 \mu m$ . Ratio of intrinsic diffusivities can be calculated in such a way (Eq.16 in [2]):

$$\frac{D_{Cu}^{*}}{D_{Zn}^{*}} \approx \frac{\sum_{j=1}^{N} X_{j} - X_{K}(1 - C_{i})\sqrt{\pi}}{\sum_{j=1}^{N} X_{j} + C_{i}X_{K}\sqrt{\pi}} \approx 0.56 < 1,$$
  
$$C_{i} = 8/13 = C_{Zn}, \qquad (11)$$

where N = 3 is formed phases quantity,  $X_j$  is phase *j*'s thickness,  $C_i$  is is the average concentration of Zn in phase *i*, or (Eq.15 in [2]):

$$\frac{D_{Cu}^{*}}{D_{Zn}^{*}} = \frac{\sqrt{D_{2}^{*t} - X_{K}(1 - C_{2})\sqrt{\pi}}}{\sqrt{D_{2}^{*t} + C_{2}X_{K}\sqrt{\pi}}} \approx 0.62.$$
(12)

Experimentally obtained ratio  $D^*_{Cu'}D^*_{Zn} \approx 0.6$  in  $\alpha$ -brass [24] and in  $\gamma$ -brass [25], so Eqs. 11 and 12 can be applied for other systems.

#### II.2. The Cu-Sn system

Another experiment was described in [3]. Phase 1 is formed between Cu and phase 2 during isothermal annealing at temperature T = 200 °C within 10 days:  $X_I \approx$ 12.6 µm,  $X_K \approx$  4.9 µm;  $C_I = 3/4$ ,  $C_2 = 6/11$ . The mutual diffusion penetrability of phase1 can be calculated by Eq. 6:

$$K_{1}^{(1phase)} = \frac{X_{1}^{2}}{t} \approx 184 \times 10^{-18} m^{2} / s \approx \frac{2(1 - C_{2})D_{1}^{*}\Delta C_{1}}{(1 - C_{1})(C_{1} - C_{2})},$$
  
$$D_{1} \approx \frac{(1 - C_{1})(C_{1} - C_{2})}{t} \frac{X_{1}^{2}}{s} \approx 10.3 \times 10^{-18} m^{2} / s, \qquad (13)$$

$$D_{1} \approx \frac{(1 - C_{1})(C_{1} - C_{2})}{2(1 - C_{2})} \frac{m_{1}}{t} \approx 10.3 \times 10^{-18} m^{2} / s, \qquad (13)$$

 $D_I^* = D_I / \Delta C_I \approx D_I / 0.012[6] \approx 860 \times 10^{-18} \text{m}^2/\text{s}$ . Ratio  $D^*_{Sn} / D^*_{Cu}$  in phase 1 can be calculated:

$$\frac{D_{Sn}^{*}}{D_{Cu}^{*}} \approx \frac{\sum_{j=1}^{N} X_{j} - X_{K}(1 - C_{1})\sqrt{\pi}}{\sum_{j=1}^{N} X_{j} + C_{1}X_{K}\sqrt{\pi}} \approx 0.74 < 1,$$

$$C_{1} = 3/4 = C_{Cu}, \quad N = 2.$$
(14)

Experimentally determined value in phase 1 according [3] is :  $D^*_{Sn} \approx 0.4 \div 0.5D^*_{Cu}$ . Ref. [9] reported that Cu has a higher tracer diffusion coefficient than Sn in the Cu<sub>3</sub>Sn phase (phase 1) at temperatures from 225 °C to 350 °C. Ratio  $D^*_{Sn}/D^*_{Cu}$  in phase 2 can also be calculated ( $X_K \approx 3\mu$ m):

 $D_2^* = D_2 / \Delta C_2 \approx 18.2 \times 10^{-18} \text{m}^2 \text{s}^{-1} / 0.021 \text{ [6]} \approx 870 \times 10^{-18} \text{m}^2 / \text{s},$ 

$$\frac{D_{Sn}^{*}}{D_{Cu}^{*}} \approx \frac{\sum_{j=1}^{N} X_{j} - X_{K} (1 - C_{2}) \sqrt{\pi}}{\sum_{j=1}^{N} X_{j} + C_{2} X_{K} \sqrt{\pi}} \approx 0.8 < 1,$$

$$C_2 = 6/11 = C_{Cu}, \quad N = 2.$$
 (15)

Experimentally determined value is as follows [3]:  $D_{Sn}^* \approx 0.31 D_{Cu}^*$  in phase 2. Otherwise, according [6, 9] the diffusivity of Sn is higher than the diffusivity of Cu at temperatures 150 °C ÷ 220 °C, and markers moves toward Sn side in phase 2. More precise estimation of ratio  $D_{Sn}^*/D_{Cu}^*$  in phase 2 needs careful experiments under hydrostatic pressure of Argon gas ( $\approx 10$  MPa) [5, 8] or under hot isostatic pressing (p  $\approx 100$  MPa, Argon) to decrease Kirkendal-Frenkel porosity formation [33].

#### III. Diffusion activation energy calculation in the Cu-Sn system

We can calculate the diffusion activation energies and the pre-exponential factors combining experimental results at the temperature  $T_2 = 357 \text{ °C}$  [6] and experimental results at the temperature  $T_1 = 200 \text{ °C}$  [3] and combining experimental results at the temperature  $T_2 = 250 \text{ °C}$  [11] and experimental results [3, 9, 6] at the temperature  $T_1 = 200 \text{ °C}$  (Table 2):

$$Q_i = \frac{RT_1T_2}{T_2 - T_1} \ln\left(\frac{D_i(T_2)}{D_i(T_1)}\right),$$



**Fig. 5.** Concentration profile of Zn change during isothermal annealing at temperature  $T = 400^{\circ}$ C within 9 h [5]:  $D_{Zn}^* > D_{Cu}^*; X_1 < X_2, X_2 = 3X_l, X_3 \approx 0; C_l = 5/6, C_2 = 8/13, C_3 = 1/2, C = C_{Zn}.$ 

Table 2

		Onishi and Fujibuchi [6]	This work	Paul <i>et al</i> . [9]	This work	Kumar <i>et</i> <i>al</i> . [3]	This work
$Q_{i,}$ kJ/mol	1=Cu <sub>3</sub> Sn	70.7	124	73.8	85.7	38.7	39.0
	$2=Cu_6Sn_5$	64.8	142	81	119.5	47.3	43.4
$D_{0i}, m^2/s$	1=Cu <sub>3</sub> Sn	1.43 x10 <sup>-8</sup>	3.77 x10⁻	2.7 x10 <sup>-9</sup>	8.7 x10 <sup>-8</sup>	-	9x10 <sup>-6</sup>
	$2=Cu_6Sn_5$	1.55 x10 <sup>-8</sup>	4	5.6 x10 <sup>-8</sup>	8.7 x10 <sup>-4</sup>	-	7x10 <sup>-5</sup>
$Q_2/Q_1$	Cu/Sn couple	0.92	8.2 x10 <sup>-2</sup>	1.1	1.4	1.22	1.11
			1.15				
$Q_1^{(1phase)}$ ,	1=Cu <sub>3</sub> Sn	78.2	78.6	-	-	-	-
kJ/mol	(Cu/Cu <sub>6</sub> Sn <sub>5</sub>						
$(T_2 = 357^{\circ}C)$	couple)						
$D_{01}, m^2/s$		1.09 x10 <sup>-6</sup>	5 x10 <sup>-9</sup>	-	-	-	-

Comparison of the diffusion activation energies and the pre-exponential factors

$$D_{0i} = D_i(T_1)e^{Q_i/(RT_1)} = D_i(T_2)e^{(RT_2)}.$$
 (16)

We can use five points ( $T_1 = 190 \ ^{o}C$ ,  $T_2 = 200 \ ^{o}C$ ,  $T_3 = 210 \ ^{o}C$ ,  $T_4 = 220 \ ^{o}C$  [6], and  $T_5 = 250 \ ^{o}C$  [11]) for calculation by the least square method:

$$Q_{i} = -\frac{5\sum_{j=1}^{5} \left(\frac{1000}{RT_{j}} \ln D_{i}(T_{j})\right) - \sum_{j=1}^{5} \ln D_{i}(T_{j}) \sum_{j=1}^{5} \frac{1000}{RT_{j}}}{5\sum_{j=1}^{5} \left(\frac{1000}{RT_{j}}\right)^{2} - \left(\sum_{j=1}^{5} \frac{1000}{RT_{j}}\right)^{2}} [kJ / mol],$$
(17)

$$D_{0i} = \exp \frac{\frac{5}{\sum_{j=1}^{5} \left(\frac{1000}{RT_j}\right)^2 \sum_{j=1}^{5} \ln D_i(T_j) - \sum_{j=1}^{5} \frac{1000}{RT_j} \sum_{j=1}^{4} \left(\frac{1000}{RT_j} \ln D_i(T_j)\right)}{5 \sum_{j=1}^{5} \left(\frac{1000}{RT_j}\right)^2 - \left(\sum_{j=1}^{5} \frac{1000}{RT_j}\right)^2} [m^2 / s]}.$$
(18)

Eqs.17 and 18 give Eqs.16 only for two points.

The data points from the Sn/Cu couple are in good agreement with the data from the incremental couples Cu/Cu<sub>6</sub>Sn<sub>5</sub> and Cu<sub>3</sub>Sn/Sn [9]. We can see a good agreement between calculations and results described in [3, 6] for one phase 1 (Cu/Cu<sub>6</sub>Sn<sub>5</sub> couple). Really, the ratio  $Q_2/Q_1$  should be less than 1 if  $D_{01} \approx D_{02}$ , as reported in [6].

The Sn diffusion coefficients in a concentrated solution (8 at. % Sn) are several times greater than Sn diffusion coefficients in dilute solution (2 at. % Sn) at temperatures from 500 °C to 650 °C [31], and diffusion activation energy of Sn vary from 89 kJ/mol to 187 kJ/mol (isotope data on Sn diffusion in a pure copper), therefore our calculated values should be correct.

# the Cuatoms at temperature 400 °C in $\gamma$ -brass Cu<sub>5</sub>Zn<sub>8</sub>, vacancies can disappear near dislocations at Zn side (sinks) and appear near dislocations at Cu side (sources), dislocations can climb, and the Kirkendall plane shifts toward Zn side. Calculated ratio $D^*_{Cu'}D^*_{Zn} \approx 0.6$ in $\gamma$ -brass Cu<sub>5</sub>Zn<sub>8</sub> is the same as experimentally obtained at temperature 400 °C.

The Cuatoms have higher intrinsic diffusivities than the Snatoms at temperature 200 °C in  $\varepsilon$ -phase Cu<sub>3</sub>Sn, vacancies can disappear near dislocations at Cu side (sinks) and appear near dislocations at Sn side (sources), dislocations can climb, and the Kirkendall plane shifts toward Cu side. Calculated ratio  $D_{Sn}^*/D_{Cu}^* \approx 0.7$  in  $\varepsilon$ -phase Cu<sub>3</sub>Sn is approximately equal to experimentally obtained at temperature 200 °C.

*Yarmolenko M.V.* - Ph.D., Associate Professor, Head of the Department of Information and Computer Technologies and Fundamental Disciplines.

#### Conclusions

The Znatoms have higher intrinsic diffusivities than

- [1] M.V. Yarmolenko, Physics and Chemistry of Solid State, 21(2), 294 (2020) (https://doi.org/10.15330/pcss.21.2.294-299).
- [2] M.V. Yarmolenko, Physics and Chemistry of Solid State, 21(4), 720 (2020) (DOI: <u>10.15330/pcss.21.4.720-726</u>).
- [3] S. Kumar, C.A. Handwerker, and M.A. Dayananda, JPEDAV 32, 309 (2011) (<u>10.1007/s11669-011-9907-91547-7037)</u>.
- [4] K.N. Tu, Electronic Thin-Film Reliability (Cambridge University Press, 2010) (https://www.amazon.com/Electronic-Thin-Film-Reliability-King-Ning-Tu/dp/0521516137).
- [5] V.V. Bogdanov, L.N. Paritskaya, and M.V. Yarmolenko, Metallofizika 12(5), 98 (1990) (<u>https://www.researchgate.net/publication/328789333\_Effect\_of\_Internal\_Stresses\_on\_Diffusion\_Phase\_Growth\_in\_Cylindrical\_Specimens</u>).
- [6] M. Onishi and M. Fujibuchi, Trans. Jpn. Inst. Met. 16, 539 (1975) (<u>https://www.jstage.jst.go.jp/article/matertrans1960/16/9/16\_9\_539/\_pdf/-char/en</u>).
- [7] Y. Wang, Y. Liu, M. Li, K.N. Tu, L. Xu, Interconnect Quality and Reliability of 3D Packaging. In: Li Y., Goyal D. (eds) 3D Microelectronic Packaging. Springer Series in Advanced Microelectronics, 64. (Springer, Singapore, 2021) (<u>https://doi.org/10.1007/978-981-15-7090-2\_17</u>).
- [8] V.V. Bogdanov, A.M. Gusak, L.N. Paritskaya, and M.V. Yarmolenko, Metallofizika 12(3), 60 (1990) (<u>https://www.researchgate.net/publication/328769306\_Osobennosti\_diffuzionnogo\_rosta\_faz\_v\_obraztsakh\_ts</u> ilindricheskoy\_formy).

- [9] A. Paul, C. Ghosh, and W.J. Boettinger, Metallurgical and materials transactions A, 42A, 952 (2011) (DOI: 10.1007/s11661-010-0592-9).
- [10] V.V. Morozovych, A.R. Honda, Yu.O. Lyashenko, Ya.D. Korol, O.Yu. Liashenko, C. Cserhati, and A.M. Gusak, Metallofiz. Noveishie Tekhnol. 40(12), 1649 (2018) (DOI: <u>10.15407/mfint.40.12.1649</u>).
- [11] O. Liashenko, A.M. Gusak, F. Hodaj, J Mater Sci: Mater Electron, 25(10), 4664 (2014) (DOI <u>10.1007/s10854-014-2221-7</u>).
- [12] G.B. Gibbs, Journal of Nuclear Materials 20(3), 303 (1966) (https://doi.org/10.1016/0022-3115(66)90042-0).
- [13] M.V. Yarmolenko, A.M. Gusak, and K.P. Gurov, Journal of Engineering Physics and Thermophysics 65, 876 (1993) (<u>https://doi.org/10.1007/BF00862930</u>).
- [14] M.V. Yarmolenko, Defect and Diffusion Forum 143-147, 1567 (1997) (<u>https://doi.org/10.4028/www.scientific.net/DDF.143-147.1567</u>).
- [15] M.V. Yarmolenko, Metallofiz. Noveishie Tekhnol. 40(9), 1201 (2018) (DOI: 10.15407/mfint.40.09.1201).
- [16] M.V. Yarmolenko, AIP Advances, 8, 095202 (2018) (<u>https://doi.org/10.1063/1.5041728</u>).
- [17] A.M. Gusak and M.V. Yarmolenko, J. Appl. Phys. 73(10), 4881 (1993) (<u>https://doi.org/10.1063/1.353805</u>).
- [18] M.V. Yarmolenko, Proceedings of an International Conference on Solid Solid Phase Transformations, 1177 (1994)
- (https://www.researchgate.net/publication/329069886\_deviation\_from\_parabolic\_growth\_of\_phase\_layers\_in\_cylindrical\_and\_spherical\_samples\_curvature\_and\_internal\_stress\_influence).
- [19] M.V. Yarmolenko, Russian Metallurgy 3, 187 (1990) (<u>https://www.researchgate.net/publication/328698369\_Stress\_in\_spherical\_samples\_with\_mutual\_diffusion</u>).
   [20] M.V. Yarmolenko, Defect and Diffusion Forum 143-147, 509 (1997)
- [20] M.V. Yarmolenko, Defect and Diffusion Forum 143-147, 509 (1997) (<u>https://doi.org/10.4028/www.scientific.net/DDF.143-147.509</u>).
- [21] A.M. Gusak, O.Yu. Liashenko, F. Hodaj, Fizika i Khimia obrabotki materialov 2, 37 (2018) (DOI:<u>10.30791/0015-3214-2018-2-37-47</u>).
- [22] M.V. Yarmolenko, Metallofiz. Noveishie Tekhnol. 42(11), 1537 (2020) (DOI: 10.15407/mfint.42.11.1537).
- [23] A.M. Gusak, Metallofiz. Noveishie Tekhnol. 42(10), 1335 (2020) (DOI: 10.15407/mfint.42.10.1335).
- [24] A.D. Smigelkas and E.O. Kirkendall, Trans. AIME 171, 130 (1947).
- [25] Ya.Ye. Geguzin,Yu. Kaganovskii, L.M. Paritskaya, and V.I. Solunskiy, Phys. Met. Metall. 47(4), 127 (1980) (<u>https://www.researchgate.net/publication/292667643\_KINETICS\_OF\_THE\_MOTION\_OF\_THE\_INTERFA\_CE\_DURING\_MUTUAL\_DIFFUSION\_IN\_A\_TWO-COMPONENT\_SYSTEM</u>)
- [26] C. Wagner, Acta Metall. 17(2), 99 (1969) (https://www.sciencedirect.com/science/article/abs/pii/000161606990131X?via%3Dihub).
- [27] B. Camin and L. Hansen, Metals, 10(8) 1034 (2020) (DOI:10.3390/met10081034).
- [28] F.J.J. Van Loo, Acta Metall. 18(10), 1107 (1970) (<u>https://www.sciencedirect.com/science/article/abs/pii/000161607090009X</u>).
   [29] G. Guy, Scripta Metall. 5(4), 279 (1971)

(https://www.sciencedirect.com/science/article/abs/pii/0036974871901943).

- [30] M.A. Dayananda, Defect Diffus. Forum, 95-98, 521 (1993) (https://www.scientific.net/DDF.95-98.521).
- [31] V. Nikulkina, A.O. Rodin, B. Bokstein, Materials Letters 257, 1265252019 (2019) (DOI: <u>10.1016/j.matlet.2019.126525</u>).
- [32] A.M. Gusak, K.N. Tu, C. Chen, Scripta Materialia 179, 45 (2020).
- (https://doi.org/10.1016/j.scriptamat.2020.01.005).

[33] A. Epishin, B. Camin, L. Hansen, J. Schmidt, Materials Science Forum 1016, 102 (2021) (DOI:<u>10.4028/www.scientific.net/MSF.1016.102</u>).

#### М.В. Ярмоленко

# Аналіз кінетики зникнення інтерметалідів та відношення внутрішніх коефіцієнтів дифузії у системах Cu-Zn та Cu-Sn

Київський національний університет технологій та дизайну, факультет ринку, інформаційних та інноваційних технологій, Черкаси, Україна, <u>yarmolenko.mv@knutd.edu.ua</u>

Теоретично проаналізована кінетика зникнення інтерметалідів у системіCu-Zn при температурі 400 °C та у системі Cu-Sn при температурах від190 °C до 250 °C. Обчислено відношення внутрішніх коефіцієнтів дифузії у системі Cu-Zn при температурі 400 °C та у системі Cu-Sn при температурі 200 °C. Знайдено також енергію активації дифузії та передекспонентні множники для системи Cu-Sn. Для аналізу були використані літературні експериментальні дані.

**Ключові слова:**дифузія, інтерметаліди, кінетика утворення фаз, мідь, цинк, олово, пористість Кіркендалла-Френкеля, зсув Кіркендалла.